This value is 10 nm for polymers doped with the dye №1. Polymer PEPK doped with the dye DCM photoluminescence intensity maximum is shifted to the right per 10–15 nm from the analogous maximum for PVE. For polymers doped with the dye №1 this value is 9–12 nm.



Fig. 8. Electroluminescence spectrum of the structure based on PPV at voltage V = 30V

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ЛЮМІНЕСЦЕНТНІ ВЛАСТИВОСТІ ОРГАНІЧНИХ БАРВНИКІВ У ПОЛІМЕРАХ РЕРК І РVE

Виготовлено сандвіч-структури для дослідження електролюмінесценції шляхом нанесення органічного шару методом центрифугування на скляну підкладку з ITO та напилення алюмінієвих контактів і зразки для дослідження фотолюмінесценції. Досліджено залежність зміни положення максимумів спектрів фотолюмінесценції від вмісту барвника і типу матричного полімеру. Знято вольт-амперні характеристики виготовлених сандвіч-структур та встановлено залежність інтегральної інтенсивності електролюмінесценції від напруги.

Ключові слова: органічний барвник, РЕРК, PVE, ITO, сандвіч-структура, OLED, фотолюмінесценція, електролюмінесценція, PPV.

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ЛЮМИНЕСЦЕНТНЫЕ СВОЙСТВА ОРГАНИЧЕСКИХ КРАСИТЕЛЕЙ В ПОЛИМЕРАХ РЕРК И РУЕ

Изготовлено сэндвич-структуры для исследования электролюминесценции нанесением органического слоя методом центрифугирования на стеклянную подкладку с ITO и напылением алюминиевых контактов и образцы для исследования фотолюминесценции. Исследовано зависимость изменения положения максимумов на спектрах фотолюминесценции от количества красителя и типа матричного полимера. Снято вольт-амперные характеристики изготовленных сэндвич-структур и установлено зависимость интегральной интенсивности электролюминесценции от напряжения. *Ключевые слова*: органический краситель, PEPK, PVE, ITO, сэндвич-структура, OLED, фотолюминесценция, электролюминесценция, PPV.

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PL AND FTIR SPECTROSCOPY OF POWDERED SILICA AEROGEL ar-SIO_X

Optical and photoluminescent properties of powdered silica aerogel $ar-SiO_x$ have been investigated using FTIR spectroscopy and PL lifetime spectroscopy. Powdered silicagel was prepared from sodium silicate water solution using sol-gel technique. It was confirmed that the investigated material consists of two phases: stoichiometric SiO_2 and non-stoichiometric SiO_x . FTIR analyses reveal the presence of numerical hydroxyle groups which determines oxidative properties of the material and makes it a promising matrix for the incorporation of nanoparticles. The intense PL emission was detected in blue-green region with stipulated peaks at 1.9, 2.0, 2.2 and 2.6 eV. It was shown that emission properties of powdered silica aerogel ar-SiO_x caused by the presence of numerical oxygen defect centres: oxygen hole centers, peroxide radicals and oxygen-deficient centers as well as siloxane and silane groups. It was also obtained that under UV treating by pulsed laser irradiation the transformation the integrated PL intensity is decreased. The PL quenching is caused by transformation of the defect structure during photo oxidation process.

Keywords: powdered silica aerogel, defect states, FTIR transmission spectroscopy, PL lifetime spectroscopy.

Introduction. It is considered that porous oxide materials, possessing a large specific surface area, high porosity and fine grain structure, can be used as a comprehensive matrix for nanoparticles incorporation and molecular adsorption in order to create luminescent nanocomposites, photodetectors, catalysts, waveguides, lasers and gas sensors [1, 5, 12, 15]. The considered

nanoporous materials are simple and inexpensive in preparation, the gas sensor sensitivity can be significantly increased due to the enlarged overall active surface area.

The fact that typical aerogels have more than 90% porosity gives them unusual characteristics: they are characterized by extremely high surface area, high thermal resistivity, low dielectric constant and low refractive index.

The instability of electroluminescence and electrophysical characteristics of the samples at voltages more than 10–15 V are found. Polymers, doped with organic dyes demonstrate characteristics, which are analogous to based on PPV structure's characteristics and can be used as a material for OLED's active layer.

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Depending on the preparation technique the silica aerogel demonstrates a strong visible PL in the blue–green region [3]. Numerous studies have been devoted to the investigation of the origin of luminescence in other SiO_2 based structures [2,17]. In fact, the structural and compositional features of the prepared silica aerogels, amorphous silica, silica xerogels and porous silica remain similar. In these materials, the ratio of surface atoms to bulk atoms is quite large, resulting in several potential light-emitting defect centres that are peculiar to the surface states. These surface related defect sites strongly affect the dynamics of the electronic transitions and will hence influence the related optical and PL properties.

In our earlier work [9] it was proved that silica aerogel has a high sensitivity with respect to liquid adsorbate and can be effectively used as transducer for chemical sensors. In this work optical and photoluminescence properties of powdered silica aerogel $ar - SiO_x$ have been investigated. The effect of UV irradiation on evolution of PL spectra has been studied.

Experiment. Powdered silica aerogel $(ar - SiO_x)$ was prepared from sodium silicate water solution and a ethanolbased catalyst [11]. The drying process was carried out in an autoclave at supercritical parameters (T=240°C and p=8·10⁶ Pa) in the presence of ethanol. These conditions are maintained for a short time with subsequent slow pressure reduction down to athmospheric pressure. As prepared material was then annealed at 450°C at oxygen athmosphere. The TEM image of porous $ar - SiO_x$ is presented on Fig. 1. In our earlier work using X-ray difraction analyses it was observed that porous aerogel $ar - SiO_x$ is the mixture of amorphous and crystal phases that consists of crystobalite and guartz.

FTIR measurements were carried out using Fourier spectrometer "Perkin-Elmer Spectrum BX" in the range of $400-4000 \text{ cm}^{-1}$ with 4 cm⁻¹ resolution.

The samples used for PL measurements were prepared by pressing of silica aerogel into pellets with diameter of about 12 mm and typical thickness of $0,2\div0,3$ mm at a pressure of 13 MPa. The temporal domain PL spectra were measured at the room temperature using the analogous registration scheme [4]. The samples were excited with nitrogen laser pulses at 337 nm (3.68 eV), repetition rate 100 Hz, pulse duration τ =8 ns and average power 20 mW. The proper band of emission was selected by a monochromator (MS2004, SOLAR TII) and registered by a combination of photomultiplier (HAMAMATSU C6270) and analog-to-digital board (up to 1 GHz sample rate). The signal was processed and analyzed by PC.



Fig. 1. TEM image of silica aerogel

FTIR spectroscopy. Fig. 2 shows FTIR transmittance spectrum of silica aerogel $ar - SiO_x$. There are absorption modes of Si - O - Si bonds with maxima at 1095, 780 and 460 cm⁻¹ and a wide band in the 3000-3700 cm⁻¹ region. The last one is due to the presence of adsorbed water and surface *OH* groups (*OH* stretching vibrations at 3440 cm⁻¹) [6,14].



Fig. 2. FTIR transmittance spectrum of silica aerogel ar-SiO_x correlated by KBr spectrum. Characteristic absorbing modes are indicated

The nature of surface groups of silica aerogel is strongly dependent on the conditions used during its preparation. In the considered aerogel $ar - SiO_x$ produced from water solution the surface is almost fully covered with hydroxyl groups.

Water molecules in interaction with silica surface groups effectively break Si - O - Si bonds forming a surface hydroxyl Si - OH groups, as a result FTIR spectrum reveals shoulders at 3600 and 940 cm⁻¹ due to presence of bounded Si - OH groups.

A weaker Si - OH bending vibration band is revealed at 1650 cm⁻¹. The FTIR spectrum reveals also the presence of absorption modes of more complex structural groups such as $Si - OCH_3$.

In Fig. 3 the result of Gaussian peak deconvolution is presented for absorption peak of Si - O - Si stretching vibration LO and TO groups. The peak in the region of 1300–850 cm⁻¹ has been revealed to have complex structure with maxima at 902, 1001, 1098 and 1201 cm⁻¹.



Fig. 3. The result of deconvolution into Gaussian profiles of stretching absorption Si-O-Si band of silica aerogel ar-SiO_x

The presence of stretching TO modes at 1098 and 1201 cm⁻¹ having a large semiwidth (110 and 96 cm⁻¹ correspondingly) suggests that investigated material consists of stoichiometric and non-stoichiometric phases SiO_2 / SiO_x .

This conclusion is consistent with the data of X-ray diffraction analyses obtained in [10]. The wavenumber of TO absorption peak is calculated from empirical solution $v(SiO_x) = 900 + 90x \ cm^{-1}$ [6], so in our case x value varies from 1.1 to 2. Absorption peak at 1201 cm⁻¹ is also shifted from 1250 cm⁻¹ for stretching LO vibrations in stoichiometric *SiO_x* structures.

Taking into consideration the huge surface area and a number of surface hydroxyl groups, silica aerogel displays acidic properties and can be used as matrix for grafting of different molecules, e.g. for chemical sensors. In earlier work [17] it was proved that silica aerogel ar-SiO_x is characterized by significant sensor response under interaction with liquid adsorbates.

PL spectroscopy. The integrated PL spectrum of the freshly prepared $ar - SiO_{v}$ sample is presented on Fig. 4. Gaussian peak decomposition of the PL spectrum reveals the presence of 4 basic peaks: Peak P1 at 1.89 eV with semiwidth (FWHM) ΔE=0.11 eV; Peak P2 at 2.08 eV (ΔE=0.16 eV); Peak P3 at 2.23 eV (ΔE=0.35 eV) and Peak P4 at 2.61 eV (Δ E=0.99 eV). The energy of all the maxima is smaller than the band gap of stoichiometric SiO₂ structure which is 8.2 eV. Howewer, in the case of nonstoichiometric structure SiO_{\star} the band gap is smaller and can reach 1.1 eV for x=0. The FTIR transmittance spectra revealed the combination of stoichiometric and nonstoichiometric phases in $ar - SiO_x$, so it should be considered that the aerogel emission is associated with the presence of a SiO_x structure (1<x<2) as well as with surface and bulk defect states in SiO₂ phase.



Fig. 4. Integrated PL spectrum of freshly prepared ar-SiO_x sample. Result of deconvolution into Gaussian profiles is shown

The structure of material and defect states are determined by preparation technology (temperature during the process of gel formation, concentration of reagents, pH level, etc.) [3,7,8]. Silica aerogels have several types of microstructural defects that can give contribution to the photoemission [3]. If PL excitation energy is 3.68 eV (nitrogen laser), the contribution to the photoemission of stoichiometric SiO_2 phase can produce only defects determined by the interaction within individual SiO_x tetrahedra. These include defects with dangling bonds: 1)

non-bounded oxygen hole center (NBOHC), which is described as follows: $\equiv Si - O_{\bullet}$ where the dot means the unpaired electron; 2) peroxide radicals (POR) $\equiv Si - O_2_{\bullet}$ and 3) oxygen-deficient centers (ODC) which include oxygen vacancies and divacancies and two-coordinate silicon (ODC(II)) [16].

Oxygen hole centers are responsible for emission in low-energy region at around 1.8–1.9 eV. (Peak P1), while the maximum at 2.7 eV (P4) is associated with the presence of two coordinate silicon in SiO, matrix. The emission peak at 2.08 eV arises due to the presence of siloxane (= Si - O - Si =) and silane (= Si - O - H) groups. These groups are formed from hydroxyl Si - OH groups connected with hydrogen bonds during the dehydration process and due to the presence of silane (SiH and SiH₂) in hydrogenated aerogels [3]. Peak P3 at 2.23 eV results from radiative recombination processes in nonstoichiometric structure SiO_x [7]. There is also the emission peak of peroxide radicals in this range.

The influence of UV irradiation on luminescence properties of $ar - SiO_x$. It was shown in our earlier work [10] that emission properties of porous composite materials based on silica aerogel essentially depend on storage conditions and external factors such as temperature, atmospheric humidity etc. Taking into consideration the fact that the PL emission properties of $ar - SiO_x$ mostly caused by the presence of oxygen bonds and oxygen centers in dielectric matrix it's important to study the influence of UV irradiation on PL properties material under investigation. For this purpose we used pulse laser irradiation (λ =337 nm, p=20 mW) focused on the sample surface with beam diameter of 3–4 mm. Fig. 5 shows the evolution of the integrated PL spectra with increasing of irradiation time.



Fig. 5 The evolution of PL spectra under pulsed UV irradiation (λ=337 nm) for ar-SiO_x sample:
 1 – initial sample and after 2–4 min; 3–8 min; 4–12 min; 5–25 min irradiation. Result of deconvolution into Gaussian profiles for spectrum 5 is shown

Taking into consideration the obtained data, it can be concluded that the interaction between oxide matrix and UV irradiation caused the decreasing of PL integrated intensity as well as changes of the PL spectral composition. The most significant changes were observed for the low-energy peak at 1.87 eV (P1), namely, after UV irradiation during 16 min there is a complete quenching of emission peak. More detailed analyses have been made through the procedure of Gauss peak decomposition. Fig. 6 shows the evolution of peak positions during the UV irradiation.



Fig. 6 The evolution of Gauss peak positions during UV irradiation for ar-SiO_xsample

It could be clearly seen that under photo oxidation process the peak positions are almost unchanged except for a small shift of PL peaks at 2.1 eV (P2) and 2.2 eV (P3) towards the high energy region. At the same time there are essential changes in the peak intensity at 1.87 and 2.2 eV, namely after 16 min irradiation the low-energy peak disappears and the P3 peak area noticeably decreases. For two another peaks (P2 and P4) essential changes haven't been observed.

Thus for powdered silica aerogel the evolution of PL spectra during photo oxidation process under UV irradiation is mainly due to the transformation of emission peaks at 1.87 and 2.2 eV.

As mentioned above, the low-energy PL emission caused by the presence of oxygen-hole centers. During photo oxidation process the transformation of these vacancies to peroxide radicals occurs according to reaction: $\equiv Si - O + O \rightarrow \equiv Si - O_2$.

It's also well known [13,16] that in amorphous siliconoxide matrix under laser excitation there is a structural reorganization, namely transformation of the oxygen vacancies type ODC(II), such as divalent silicon Si_2^{0} , and the neutral oxygen vacancies (NOV) into defect type E centers according to the scheme:

 $\equiv Si :+ \hbar \omega \rightarrow = Si^+ + e,$

$$=$$
 S i^+ + = S $i^ \implies$ \equiv S i^+ ...S i^+ = S i^-

Since the E centers can give a contribution to the photoemission under excitation energies of 5.8-6.3 eV, in our case, they are not active, which results in reducing of the peak intensity.

Thus, we can conclude that the decreasing of the integrated PL intensity of the powdered silica aerogel is caused by the transformation of the defect structure during photo oxidation process.

Conclusions. In this work optical and photoluminescence properties of powdered silica aerogel $ar - SiO_{i}$ have been investigated using FTIR and PL spectroscopy. It was confirmed that investigated material consists of stoichiometric SiO₂ and non-stoichiometric SiO₂ phases. FTIR spectra revealed a presence of numerical hydroxyl groups such as bonded Si - OH and non-bonded -OHgroups which determines oxidative properties of the material and makes it a promising matrix for incorporation of silicon nanoparticles.

Photoemission properties of investigated material are mainly due to the presence of oxygen defect states in nonstoichiometric SiO_x phase as well as siloxane and silane groups. It was shown that UV irradiation causes the decreasing of integrated PL intensity of silica aerogel mainly due to the transformation of its defect structure.

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FTIR ТА ФЛ СПЕКТРОСКОПІЯ ПОРОШКОПОДІБНОГО АЕРОГЕЛЮ КРЕМНЕЗЕМУ ar-SiO_x

Було досліджено оптичні та фотолюмінесцентні властивості порошкоподібного аерогелю кремнезему з використанням FTIR спектроскопії пропускання та фотолюмінесцентної спектроскопії. Порошкоподібний аерогель кремнезему було виготовлено на основі водного розчину силікату з використанням технології золь-гель синтезу. Підтверджено, що досліджуваний матеріал складається з двох фаз: стехіометричної SiO₂ та нестехіометричної SiOx-Aналіз FTIR спектрів пропускання виявив присутність значної кількості гідроксидних груп, що обумовлюють окиснювальні властивості матеріалу й визначають перспективність використання аерогелю кремнезему в якості ефективної матриці для інкорпорації наночастинок. Зареєстровано інтенсивну ФЛ у синьо-зеленій області спектру з максимумами при 1.9, 2.0, 2.2 та 2.6 еВ. Було показано, що емісійні властивості порошкоподібного аерогелю кремнезему ar-SiO, обумовлені наявністю значної кількості кисневих дефектних центрів, таких як кисневі діркові центри, пероксидні радикали та киснево-дефіцитні центри, а також силоксанових та силанових груп. Було також показано, що під впливом імпульсного лазерного УФ опромінення спостерігається зменшення інтегральної інтенсивності ФЛ. Гасіння ФЛ обумовлене трансформацією дефектної структури матеріалу в процесі фотоокиснення.

Ключові слова: порошкоподібний аерогель кремнезему, дефектні стани, FTIR спектроскопія пропускання, кінетика ФЛ.

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FTIR И ФЛ СПЕКТРОСКОПИЯ ПОРОШКООБРАЗНОГО АЭРОГЕЛЯ КРЕМНЕЗЕМА ar-SiO_x

Проведено исследование оптических и фотолюминесцентных свойств порошкообразного аэрогеля кремнезема с использованием FTIR спектроскопии пропускания и фотолюминесцентной спектроскопии. Порошкообразный аэрогель кремнезема изготавливался на основе водного раствора силиката с использованием технологии золь-гель синтеза. Подтверждено, что исследуемый материал состоит из двух фаз: стехиометрической SiO₂ и нестехиометрической SiO₂ и нестехиометрической SiO₄. Анализ FTIR спектров пропускания обнаружил присутствие значительного количества издоржидных групп, которые обуславливают окиспителные свойства материал и определяют песпективность его использования в качестве матрицы для инкорторирования наночастии. Зарегистрирована интенсивная ФЛ в сине-зеленой области спектра с максимумами при 1.9, 2.0, 2.2 и 2.6 эВ. Было показано, что эмиссионные свойства порошкообразного аэрогеля кремнезема и сиспородно-дефицитные центры, а также силородных дефектных центров, таких как киспородные дырочные центра, пероксидные радикалы и киспородно-дефицитные центры, а также силоксановые и илановые группы. Было также показано, что под воздействием импульсного лазерного УФ облучения наблюдается уменьшение интегральной интенсивная то под воздействием импульсного лазерного УФ облучения наблюдается уменьшение интегральной интенсивнае споса: порошкообразный арогель кремнезема, дефектные состояния, КТІК спектроскопия пролусканния, кинетика ФЛ.

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VISUALIZATION OF MAGNETO-ELECTRIC DISPLAYS IN FG/GGG EPITAXIAL STRUCTURES

Using the method of polarizing microscopy, under the combined effects of static and alternating electric fields and magnetic field, studied the reaction of the domain structure (DS) epitaxial ferrite garnet (FG) films, grown on single crystal substrates of gallium-gadolinium garnet (FG / GGG). In transmitted light visually detected a small effect of the profile changes ("smearing") of the individual local sites of the films domain wall (DW) because of a combination of three-channel external influence.

Keywords: magneto-electric effect, electric field, magnetic field, domain wall, domain structure, polarizing microscope.

Introduction. The change of magnetization under the influence of electric field or of electric polarization under the influence of magnetic field are called magnetoelectric (ME) effect. Study of the mechanism of interaction of electric and magnetic subsystems in magneto-electric materials has recently been the subject of many publications. This interest is driven by a need to establish a single fundamental theory of magneto-electric interactions in solids, and wide application possibilities of using magneto-electric materials in electronics.

The first explicit prediction of ME effect in a specific material was made by Dzyaloshinskii who showed that in Cr₂0₃ these effects are allowed by the magnetic symmetry [2]. Experimentally, the electrically induced ME effect was first observed by Astrov [1] on a crystal of Cr₂0₃ and later Rado and Folen [10]. The first observation of the ME effect in yttrium-iron-garnets (YIG) was reported by O'Dell [9] and later, the ME effect was studied in a number of papers [3÷8, 12]. The external electric field that connected to the crystal of certain magnetic symmetry (eg, YIG), can cause in crystal the manifestations induced optical phenomena, linear or nonlinear in the electric field. One of such phenomenon is the effect of the changes of light polarization plane Faraday rotation in an optically transparent dielectric crystal induced by an electric field, which the authors named as an electromagneto-optical (EMO) effect [8]. Using a highly sensitive method of optical polarimetry, it is possible to measure the changes of light polarization plane rotation in an external electric field, as well as to carry out visual observations of the domain structure of the sample using a polarizing microscope.

Iron garnets are a large class of ferrimagnetic oxides with high Curie temperature (T_c >500K) and have been applied to magneto-optical devices and magnetic bubble memories [11, 13]. The active interest in the structural, magnetic, and magneto-optical properties of garnet films has been related to the fact that all these properties can be widely varied by changing the composition and orientation. Although the parent garnet crystal structure is characterized as the cubic centrosymmetric space group the studies of film structure and magnetic properties have revealed that films tend to have uniaxial or orthorhombic

symmetry. The origin of this symmetry lowering is due to growth anisotropy and mismatch between the lattice parameters of the films and substrates. The crystallographic orientation of the substrate is also of primary importance. Garnet crystals are well known to play an important role in technological devices.

Domain structure (DS) of ferrite garnets is periodically interspersed with small regions of antiparallel magnetization direction, which are separated by domain walls. In DW is changing the direction of the orientation of the spins in the same domain to the direction in the nearby. In ferrite garnets it is possible to visualize processes occurring in them due to the magneto-optical Faraday effect.

In this paper, we report the results of studies ME manifestations in epitaxial ferrite garnet films in a twochannel and three-channel external influence. In particular, visual observations were made for the DS of the film with the use of magneto-optical polarization microscopy with high optical permission based on the Faraday effect in two experimental versions: 1) under the joint action of the alternating electric field and constant magnetic field; 2) under the joint action of DC and AC electric field and a constant magnetic field. Investigated epitaxial films grown on (111) substrates of gallium-gadolinium garnets (GGG). The domain structure of the films studied under the polarizing microscope looks like high contrast, which indicates about significant deviation of domain magnetization vectors from the film plane.

Experimental. The test sample was placed between two optically transparent electrodes. The electrodes were deposited by spraying on the inner surfaces of the two thin glass plates. Separately or simultaneously to the sample plugged in the AC and DC voltage. External constant magnetic field was oriented along the plane of the film. The thickness of the film was about 10 μ m, the width of domains was about 14 μ m at H=0, and the domain-wall width was about 0.5 μ m. The test sample we previously several times been the iterative process of quasi-static magnetization in the magnetic field in both directions. The reproducibility of the overall picture domain labyrinth structure in this case was not observed. DW motion occurred intermittently due to the interaction with micro-